

# LONGLITE® DRY FILM PHOTO RESIST

## FF-9040S

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## **LONGLITE®Dry Film Photo Resist FF-9040S** It is a negative type, water-soluble dry film photoresist.

With good resolution and adhesion, it is suitable for fine line acid etching, Tenting, copper electroplating and other printed circuit board processes.

### characteristic:

1. Has excellent resolution.
2. Has excellent adhesion and covering power.
3. It has excellent chemical resistance and electroplating resistance.
4. The membrane is flexible, Tenting Excellent properties.
5. Very low pollution to the plating solution.
6. The color contrast is obvious after exposure.

### Specification:

Type	FF-9040S
Resist thickness	38 $\mu$ m (1.5 mil)
Standard width	0.125 inch
length	500ft / roll

### store:

It is recommended to place it horizontally in a dry refrigerator. Storage environment conditions: temperature 5~20°C, relative humidity 50 $\pm$ 10%.

### Safety rules for use:

1. exist UV-free When not in use, it should be covered with a light-proof cloth and stored horizontally.
2. Odors will be generated during film pressing, so attention should be paid to the exhaust of the film pressing room.
3. Skin contact with the photoresist layer may cause irritation, so avoid direct contact. Wash your hands with soap after use. If irritation persists, seek medical attention.

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LONGLITE® Dry Film Photo Resist Changchun Company and Tokyo Ohka Industry Co., Ltd. Tokyo Ohka Kogyo Co., Ltd.) Technical cooperation production.

## Test items:

### 1.Imaging time,Break Point

2.Reproducibility under different exposure energies - sensitivity, resolution (line spacing), adhesion (line width), dry film line width changes

3.Stripping characteristics

4.Hair color concentration

5. Tentingcharacteristic

## Test Conditions:

1.Substrate: 1.6 mm D/S (Copper thickness35 $\mu$ m)

2.Pre-treatment: Oscillation Buffering Polish (3M #320 # 500)

3.Preheat: Batch type oven, 80°C,10 min Roller (The substrate surface temperature before lamination is about50°C)

4.Lamination: temperature:100°C

Roller pressure:4.0 kg/cm<sup>2</sup>

speed:2.0 M/min

5. Hold time: After lamination15 min

6.Exposure: UVE-M500 5KW Ultra High Pressure Mercury Lamp

7. Hold time: After exposure15 min

8.Imaging: Developer:1% Na<sub>2</sub>CO<sub>3</sub>aq

temperature:29 $\pm$ 1°C

Spray pressure:1.2~1.4kg/cm<sup>2</sup>

BP:50%

9.Stripping film: Stripping solution:2.0%,3.0%,4.0% NaOH

temperature:40°C,50°C,60°C Spray pressure:

Immersion

1. Imaging time, Break Point

Break Point	23sec
Imaging time (2 BP)	46sec

2. Reproducibility at different exposure energies:

project	Sensitivity	Resolution (line spacing)	Adhesion (line width)	Dry film line width variation
unit	(Step)	( $\mu\text{m}$ )	( $\mu\text{m}$ )	( $\mu\text{m}$ )
Exposure (mJ/cm <sup>2</sup> )	20	4	50	- 1
	30	5	50	0
	40	6	50	1
	50	7	50	3
	60	7.5	60	5
	70	8	60	7
	80	8.25	60	9
	90	8.5	80	11
	100	9	80	13

Remark:

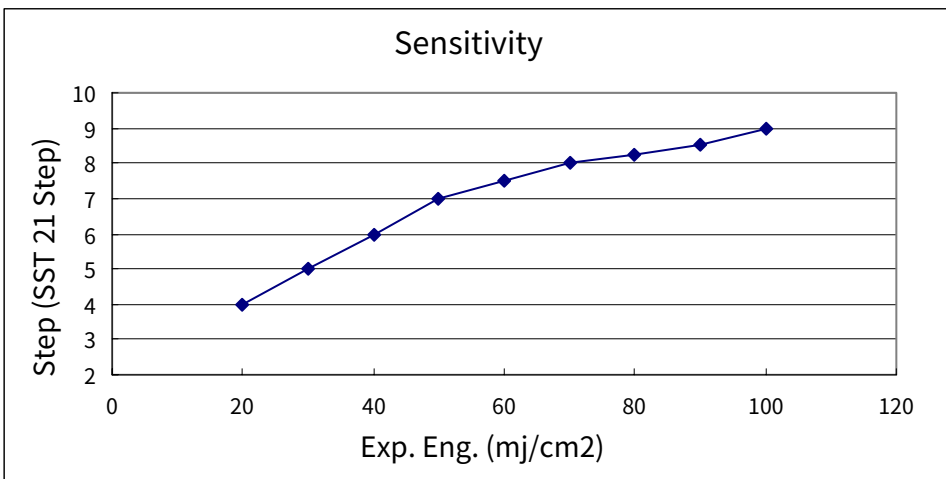
a. Data for reference

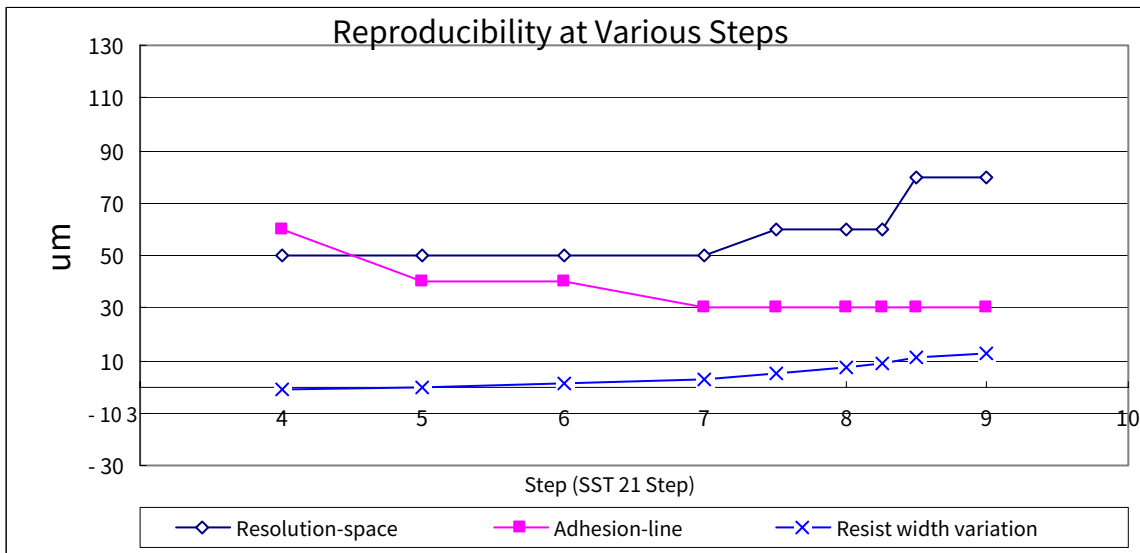
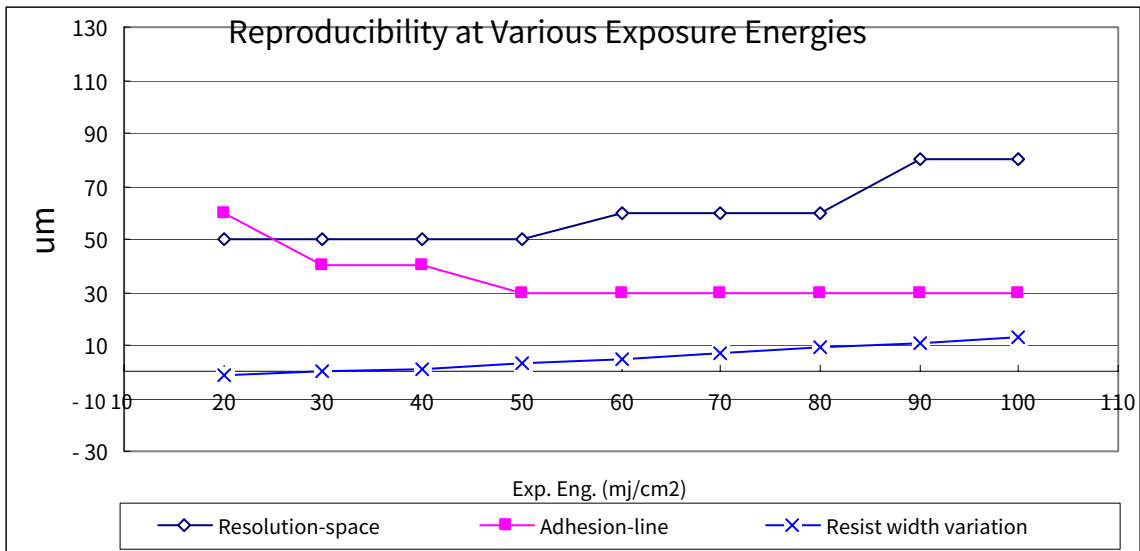
b. Sensitivity: Stouffer 21 Segment exposure table (Stouffer 21 steps sensitivity guide) Place directly on dry film, record the remaining step.

c. Resolution: Test Film CCP Pattern-1 (L/S=2/1), L Font line, 20~200 $\mu\text{m}$ .

d. Adhesion: Test film CCP Pattern-1 (L/S=1/2), L Font line, 20~200 $\mu\text{m}$ .

e. Dry film line width change: Calculate the difference between the line width of the dry film after development and the line width of the test film. Test film: L/S = 100/200 $\mu\text{m}$ .





3. Stripping characteristics

Stripping solution concentration \ Stripping solution temperature	40°C		50°C		60°C	
	Stripping time (sec)	Peel sheet shape	Stripping time (sec)	Peel sheet shape	Stripping time (sec)	Peel sheet shape
2%	49-54	Fragments	39-44	Fragments	32-34	Fragments
3%	41-48	Flakes with broken mouth	36-40	Fragments	30-33	Fragments
4%	38-49	Whole piece	33-38	Flakes with broken mouth	25-29	Flakes with broken mouth

4. Hair color concentration

Before exposure	0.07
After exposure (8 Step)	0.37

5. Tenting characteristic

strength(g)	349
time(sec)	3.50

Remark:

- a. Data for reference
- b. Exposure: 8 Step
- c. Gauge:  $\phi 2\text{mm}$ .
- d. Speed: 10mm/min.
- e. Board:  $\phi 6\text{mm}$ , thickness 1.6mm.

Recommended operating conditions:

**Surface treatment:**

Type: Chemical micro-etching or grinding

Water break test: at least 15~30 sec (upright)

If there is still water on the board surface, do not blow dry it directly with hot air.

Recommended surface roughness:  $R_a=0.2\sim 0.4\mu\text{m}$ ,  $R_z=1.5\sim 2.5\mu\text{m}$ .

**Lamination:**

Film application temperature: 55~65°C

Roller temperature:  $110\pm 10^\circ\text{C}$

Film pressure: 2~5 kg/cm<sup>2</sup>

Roller pressure: 3~5 kg/cm<sup>2</sup>

Film application time: 1.5~2 sec

speed: 1.0~3.0 m/min

Board temperature: 40~60°C

Board temperature: 45~65°C

Holding time1: 15 min~24 hr (  $23\pm 2^\circ\text{C}$ ,  $50\pm 10\%$  RH)

If the board temperature exceeds 70°C, the dry film on the plated through hole may become thinner. Please follow the instructions

in the laminator manual when adjusting the roller temperature and pressure. After lamination, the substrate should be placed

upright to cool to room temperature.

If the substrate after lamination is yellow UV-free Place the light source over 6 hr, be sure to cover the substrate with opaque cloth.

**exposure:**

Step: 6~9 step (SST 21 Step)

Holding time2: 15 min~24 hr (  $23\pm 2^\circ\text{C}$ ,  $50\pm 10\%$  RH)

Holding time1 and Holding time2 The total should be less than 2 sky.

**Imaging:**

Developer: 0.7~1.0 wt% Na<sub>2</sub>CO<sub>3</sub>

temperature: 26~30°C

Spray pressure: 1.2~2.0 kg/cm<sup>2</sup>

Image point: 1/2~2/3

Recommended washing temperature 15-25°C, water washing spray pressure 1.2-2.0 kg/cm<sup>2</sup>

Adjust the flow rate of the water washing tank to control the first water washing tank to

maintain pH 8 Dry film load: less than 10g/L.

**Etching:**

Type: Cupric chloride or ferric chloride acid etching solution

**Stripping film:**

Stripping fluid: 3.5±0.5 wt% NaOH or KOH

temperature: 50~55°C

Spray pressure: 1.5~3.0 kg/cm<sup>2</sup>

Stripping point: 1/2~2/3

Dry film loading is less than 20g/L.

It is recommended that the water washing spray pressure is greater than 1.0kg/cm<sup>2</sup>.